PATENT

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicants

Shin Hwa Li et al.

Filed

December 22, 2003

For

SEMICONDUCTOR STRUCTURE HAVING AN

IMPROVED PRE-METAL DIELECTRIC STACK AND

METHOD FOR FORMING THE SAME

Docket No.

: 98-P-009D1 (850063.529D1)

Date

: December 22, 2003

Mail Stop Patent Application Commissioner for Patents P.O. Box 1450 Alexandria, VA 22313-1450

INFORMATION DISCLOSURE STATEMENT

Commissioner for Patents:

In accordance with 37 C.F.R. §§ 1.56 and 1.97 through 1.98, applicants wish to make known to the Patent and Trademark Office the 25 references set forth on the attached Form PTO-1449. This application relies, under 35 U.S.C. § 120, on the earlier filing date of prior Application No. 09/632,388, filed August 3, 2000. The references listed on the attached Form PTO-1449 were submitted to and/or cited by the Patent and Trademark Office in this prior application and, therefore, are not required to be provided in this application. If the Examiner wishes, copies will be provided upon request. As to any reference supplied, applicants do not admit that it is "prior art" under 35 U.S.C. §§ 102 or 103, and specifically reserve the right to traverse or antedate any such reference, as by a showing under 37 C.F.R. § 1.131 or other method. Although the aforesaid references are made known to the Patent and Trademark Office in compliance with applicants' duty to disclose all information they are aware of which is believed relevant to the examination of the above-identified application, applicants believe that their invention is patentable.

Please acknowledge receipt of this Information Disclosure Statement and kindly make the cited references of record in the above-identified application.

Applicants believe this Information Disclosure Statement has been timely filed, however, the Director is authorized to charge any fee due by way of this Information Disclosure Statement to our Deposit Account No. 19-1090.

Respectfully submitted,

Seed Intellectual Property Law Group PLLC

David V. Carlson

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DVC:lcs

Enclosures:

Postcard Form PTO-1449

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Sheet <u>1</u> of <u>2</u>

FORM PTO-1449 (REV.7-80)	U.S. DEPARTMENT OF COMMERCE PATENT AND TRADEMARK OFFICE				ATTY. DOCKET NO. A. 98-P-009D1 (850063.529D1)		APPLICATION NO.		
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